

High spatial resolution graded-gap $\text{Al}_x\text{Ga}_{1-x}\text{As}$ X-ray imaging detector

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The new type, high spatial resolution graded-gap $\text{Al}_x\text{Ga}_{1-x}\text{As}$ imaging detector is constructed with an intent to use it for X-ray microbeam radiation therapy (MRT).

The detector consists of low-doped graded-gap p- $\text{Al}_x\text{Ga}_{1-x}\text{As}$ layer, thin high-doped p^+ -GaAs layer at the narrow gap side of graded-gap layer and thin p- $\text{Al}_x\text{Ga}_{1-x}\text{As}$ layer on the top of the structure. The charge generated by X-ray beam in graded-gap p- $\text{Al}_x\text{Ga}_{1-x}\text{As}$ layer is collecting in thin p^+ -GaAs layer by graded-gap field. $\text{Al}_x\text{Ga}_{1-x}\text{As}$ top layer restricts penetration of collected charge to the surface of the structure. The X-ray luminescence from the thin p^+ -GaAs layer through the p- $\text{Al}_x\text{Ga}_{1-x}\text{As}$ top layer is detecting by CCD camera. Because of small distance of luminescent p^+ -GaAs layer from the surface of the detector and small angle of total internal reflection (16° for GaAs), optical spread of image is negligible ($0.5 \mu\text{m}$). The factor responsible for edge unsharpness of X-ray image is the diffusion of electrons in graded-gap $\text{Al}_x\text{Ga}_{1-x}\text{As}$ layer. Electron diffusion spreading in graded-gap $\text{Al}_x\text{Ga}_{1-x}\text{As}$ layer of thickness $20 \mu\text{m}$ and variation of Al fraction from 0.4 to 0 is estimated as $6 \mu\text{m}$.

The experimental measurement of X-ray images shows the spatial resolution better than 25 line/mm.

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